

Abstract

Provided is a method of manufacturing a solar cell, by which a texture can be formed on the surface of a silicon substrate uniformly. In this invention, the method is characterized by including steps of: immersing the silicon substrate (2) in a first aqueous solution containing hydrofluoric acid to remove a natural oxide film on the surface of the silicon substrate (2); immersing the silicon substrate (2) from which the natural oxide film has been removed in a second aqueous solution containing the metal ions to deposit the metal ions on the surface of the silicon substrate (2) by electroless plating; and immersing the silicon substrate (2) having the metal ions deposited thereon in a third aqueous solution containing hydrofluoric acid and hydrogen peroxide water to form a porous layer (3) on the surface of the silicon substrate (2) by a catalytic reaction with the metal ions.